

IN THE CLAIMS

Please amend the claims as follows:

1. (original) A method of producing a conductive layer (5) on a substrate (1), comprising the steps of:

defining a groove (3) for the conductive layer (5) using a photodefinable insulator material (2); and

filling the groove (3) with a material capable of forming the conductive layer (5).

2. (original) A method according to claim 1, wherein the step of defining the groove (3) comprises:

depositing the insulator material (2) onto the substrate (1);

defining a pattern in the insulator material; and

processing the pattern to form the groove (3).

3. (currently amended) A method according to claim 1-~~or 2~~, comprising filling the groove (3) using a blading technique.

4. (currently amended) A method according to ~~any one of the preceding claims~~claim 1, wherein the material capable of forming the conductive layer (5) comprises a metal precursor.

5. (currently amended) A method according to ~~any one of~~  
~~claims 1 to 3~~claim 1, wherein the material capable of forming the conductive layer (5) comprises a conductive ink.

6. (currently amended) A method according to claim 4-~~or 5~~, further comprising curing the material to obtain the conductive layer (5).

7. (original) A method according to claim 6, further comprising etching the insulator material to reduce its thickness relative to the thickness of the conductive layer.

8. (currently amended) A method according to claim 6-~~or 7~~, comprising depositing one or more further functional layers over the conductive layer.

9. (currently amended) A method according to ~~any one of the preceding claims~~claim 1, wherein the conductive layer comprises a row or column line in an active matrix liquid crystal display.

10. (currently amended) An active matrix liquid crystal display including a conductive layer made by a method according to any one of the preceding claimsclaim 1.

11. (original) A device comprising a substrate (1) overlaid with a photodefinable insulator material (2), the material having a groove (3) for a conductive layer (5) defined therein.

12. (original) A device according to claim 11, further comprising a conductive layer (5) in the groove (3).

13. (currently amended) A device according to claim 11 or 12, comprising an active matrix liquid crystal display.

14. (original) A method of producing a conductive layer (5) on a substrate (1), comprising the steps of:

defining a groove (3) for the conductive layer (5); and  
blading a material capable of forming the conductive layer (5) into the groove.

15. (original) A method according to claim 14, comprising defining the groove (3) by printing an insulating material onto the substrate.

16. (original) A method according to claim 14, wherein the step of defining the groove (3) includes depositing a material (2) onto the substrate (1) and defining the groove (3) in the material.

17. (original) A method according to claim 16, wherein the material (2) comprises a photodefinable material.

18. (currently amended) A method according to ~~any one of claims 14 to 17~~claim 14, wherein the substrate comprises a substrate for use in an active matrix liquid crystal display.

19. (original) A method of producing a conductive layer (5) on a substrate for an active matrix liquid crystal display, the method comprising the steps of printing an insulating material (10) onto the substrate (1) such that the printed material defines a groove (3) for the conductive layer and filling the groove with a material capable of forming the conductive layer (5).